# 10654980\_LIST

PLUS Search Results for S/N 10654980, Searched March 30, 2004

The Patent Linguistics Utility System (PLUS) is a USPTO automated search system for U.S. Patents from 1971 to the present. PLUS is a query-by-example search system which produces a list of patents that are most closely related linguistically to the application searched. This search was prepared by the staff of the Scientific and Technical Information Center, SIRA.

## 10654980\_CLS

# Most Frequently Occurring Classifications of Patents Returned From A Search of 10654980 on March 30, 2004

# **Original Classifications**

- 4 424/45
- 3 128/200.18
- 3 128/200.21
- 2 216/42
- 2 424/130.1

# **Cross-Reference Classifications**

- 4 128/200.14
- 4 128/203.12
- 3 128/200.18
- 3 128/200.21
- 3 216/24
- 2 55/486
- 2 128/203.15
- 2 128/203.28
- 2 216/11
- 2 424/46
- 2 424/489
- 2 438/20
- 2 438/739
- 2 438/945
- 2 445/51

#### **Combined Classifications**

- 6 128/200.18
- 6 128/200.21
- 4 128/200.14
- 4 128/203.12
- 4 424/45
- 3 128/203.15
- 3 216/11
- 3 216/24
- 3 216/42
- 2 55/486
- 2 95/286
- 2 128/203.28
- 2 239/34
- 2 356/342
- 2 424/130.1
- 2 424/46
- 2 424/489
- 2 438/20
- 2 438/739
- 2 438/945
- 2 445/51

#### 10654980\_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned From A Search of 10654980 on March 30, 2004

6 128/200.18 (3 OR, 3 XR)

Class 128: SURGERY

128/200.14 LIQUID MEDICAMENT ATOMIZER OR SPRAYER

128/200.18 .Spray impinged against baffle in or adjacent

flow conduit

6 128/200.21 (3 OR, 3 XR)

Class 128: SURGERY

128/200.14 LIQUID MEDICAMENT ATOMIZER OR SPRAYER

128/200.21 .Gas stream aspirating medicament from

reservoir

4 128/200.14 (0 OR, 4 XR)

Class 128: SURGERY

128/200.14 LIQUID MEDICAMENT ATOMIZER OR SPRAYER

4 128/203.12 (0 OR, 4 XR)

Class 128: SURGERY

128/200.24 RESPIRATORY METHOD OR DEVICE

128/203.12 .Means for mixing treating agent with

respiratory gas

4 424/45 (4 OR, 0 XR)

Class 424: DRUG, BIO-AFFECTING AND BODY TREATING

**COMPOSITIONS** 

424/43 EFFERVESCENT OR PRESSURIZED FLUID CONTAINING

424/45 .Organic pressurized fluid (e.g., freons, etc.)

3 128/203.15 (1 OR, 2 XR)

Class 128: SURGERY

128/200.24 RESPIRATORY METHOD OR DEVICE

128/203.12 .Means for mixing treating agent with

respiratory gas

128/203.15 ... Particulate treating agent carried by

breathed gas

3 216/11 (1 OR, 2 XR)

Class 216: ETCHING A SUBSTRATE: PROCESSES

216/11 FORMING OR TREATING AN ARTICLE WHOSE FINAL

**CONFIGURATION HAS A PROJECTION** 

3 216/24 (0 OR, 3 XR)

Class 216: ETCHING A SUBSTRATE: PROCESSES

216/24 FORMING OR TREATING OPTICAL ARTICLE

3 216/42 (2 OR. 1 XR)

Class 216: ETCHING A SUBSTRATE: PROCESSES

216/41 MASKING OF A SUBSTRATE USING MATERIAL RESISTANT

TO AN ETCHANT (I.E., ETCH RESIST)

216/42 .Resist material applied in particulate form or

spray

2 55/486 (0 OR, 2 XR)

#### 10654980\_CLSTITLES

Class 055: GAS SEPARATION

TWO OR MORE SEPARATORS (E.G., SPACED FILTERS IN 55/482

FLOW LINE OR CASING)

55/486 .Plies or layers of different characteristics

or orientation

2 95/286 (1 OR, 1 XR)

Class 095: GAS SEPARATION: PROCESSES

95/273 **FILTERING** 

95/286 .Plural separate media

2 128/203.28 (0 OR, 2 XR)

Class 128: SURGERY

128/200.24 RESPIRATORY METHOD OR DEVICE

128/203.12 .Means for mixing treating agent with

respiratory gas

128/203.28 ..Including expandable bag, bellows, or squeeze

bulb

2 239/34 (1 OR, 1 XR)

Class 239: FLUID SPRINKLING, SPRAYING, AND DIFFUSING

239/34 **SLOW DIFFUSERS** 

(1 OR, 1 XR) 2 356/342

Class 356: OPTICS: MEASURING AND TESTING

BY PARTICLE LIGHT SCATTERING 356/337

.With photocell detection 356/338 356/342 ..Of back-scattered light

2 424/130.1 (2 OR, 0 XR)

Class 424: DRUG, BIO-AFFECTING AND BODY TREATING

**COMPOSITIONS** 

424/130.1 IMMUNOGLOBULIN, ANTISERUM, ANTIBODY, OR

ANTIBODY FRAGMENT, EXCEPT CONJUGATE OR COMPLEX OF THE SAME

WITH NONIMMUNOGLOBULIN MATERIAL

2 424/46 (0 OR, 2 XR)

Class 424: DRUG, BIO-AFFECTING AND BODY TREATING

**COMPOSITIONS** 

424/43 **EFFERVESCENT OR PRESSURIZED FLUID CONTAINING** 

424/45 .Organic pressurized fluid (e.g., freons, etc.)

424/46 .. Powder or dust containing

2 424/489 (0 OR, 2 XR)

Class 424: DRUG, BIO-AFFECTING AND BODY TREATING

**COMPOSITIONS** 

424/400 PREPARATIONS CHARACTERIZED BY SPECIAL PHYSICAL

**FORM** 

424/489 .Particulate form (e.g., powders, granules,

beads, microcapsules, and pellets)

2 438/20 (0 OR, 2 XR)

Class 438: SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/20 **ELECTRON EMITTER MANUFACTURE** 

2 438/739 (0 OR, 2 XR)

## 10654980\_CLSTITLES

Class 438: SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)
438/735 .Differential etching of semiconductor

substrate

438/737 ...Substrate possessing multiple layers

438/738 ....Selectively etching substrate possessing

multiple layers of differing etch characteristics

438/739 .....Lateral etching of intermediate layer

(i.e., undercutting)

2 438/945 (0 OR, 2 XR)

Class 438: SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/942 MASKING

438/945 .Special (e.g., metal, etc.)

2 445/51 (0 OR, 2 XR)

Class 445: ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR

**DEVICE MANUFACTURING** 

445/1 PROCESS

445/46 .Electrode making

445/51 ..Emissive type